

Part Number

Customer

Category	Parameter	Specification	Measurement Method	
OverallWafer	1.0	Diameter	150.00 +/- 0.50 mm	
	2.0	Primary Flat Orientation	{110} +/- 1 degree	Wafer Vendor
	3.0	Primary Flat Length	57.50 +/- 2.50 mm	Wafer Vendor
	4.0	Secondary Flat Orientation	semi/none	
	5.0	Overall Thickness	303.00 +/- 16.00 $\mu$ m	ADE, 100%
	6.0	Total Thickness Variation (TTV)	<5.00 $\mu$ m	Guaranteed by Process
	7.0	Bow	<80.00 $\mu$ m	ADE to ASTM F534 (Best fit), 20%
	8.0	Warp	<80.00 $\mu$ m	ADE to ASTM F534 (Best fit), 20%
	9.0	Edge Chips	0	Bright Light, 100%
	10.0	Edge Exclusion	5mm	
HandleSilicon	11.0	Handle Growth Method	CZ	Wafer Vendor
	12.0	Handle Orientation	{100} +/- 1degree	Wafer Vendor
	13.0	Handle Thickness	300.00 +/- 15.00 $\mu$ m	ADE, 100%
	14.0	Handle Doping Type	P	Wafer Vendor
	15.0	Handle Dopant	Boron	Wafer Vendor
	16.0	Handle Resistivity	1~ 30 Ohmcm	Wafer Vendor
	17.0	Backside Finish	Polished with oxide, lasermark, and light handling marks	Wafer Vendor
BuriedOxide	18.0	Oxide Type	Thermal	
	19.0	Oxide Thickness	10,000.00 +/- 500.00 A	Nanospec centre point, 4%
	20.0	Oxide formed on	Handle only	
DeviceSilicon	21.0	Device Growth Method	FZ	Wafer Vendor
	22.0	Device Orientation	{100} +/- 1degree	Wafer Vendor
	23.0	Nominal Thickness	2.00 +/- 0.50 $\mu$ m	FTIR, 100% 9-Pt (note3)
	24.0	Distance to device silicon edge from wafer edge	<= 2mm	Typical by Process
	25.0	Device Doping Type	Any	Wafer Vendor
	26.0	Device Dopant	Any	Wafer Vendor
	27.0	Device Resistivity	>10,000 Ohmcm	Wafer Vendor
	28.0	Voids	none	Wafer Vendor
	29.0	Scratches	<10mm total length	Bright Light, 100% (note 2)
	30.0	Haze	none	Bright Light, 100% (note 2)

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Shipping Details	Wafer per box :	Max 25	
	Packaging :	Taped Polypropylene Wafer Box Empak, Ultrapak, 150.00mm Antistatic Double Bagging	
	Lot Shipment Data	Device Thickness Bow / Warp Data Handle and SOI Thickness	



Explanatory Notes 1. Microscope inspection performed using microscope scan as below. 5x objective.

2. All bright light inspections performed exclude all wafer area outside the edge exclusion defined in Overall Wafer, Edge Exclusion. High intensity bright lamp inspection as per ASTM F523.

3. 9 point measurement are as shown in the diagram below:



Additional Information